

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Priority Application Serial No. .... 10/094,580  
Priority Filing Date ..... March 6, 2002  
Inventor ..... Cem Basceri et al.  
Assignee ..... Micron Technology, Inc.  
Priority Group Art Unit..... 2818  
Priority Examiner ..... David Nhu  
Attorney's Docket No. ..... MI22-2407  
Title: Plasma Enhanced Chemical Vapor Deposition Method of Forming a  
Titanium Silicide Comprising Layer (as Amended)

PRELIMINARY AMENDMENT

To: Mail Stop Patent Application  
Commissioner for Patents  
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VIA EXPRESS MAIL

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Please enter the following amendments prior to examining the above-  
identified application.

AMENDMENTS